Abstract

STAGE APPARATUS, EXPOSURE APPARATUS, EXPOSURE METHOD, AND DEVICE FABRICATION METHOD

There is provided a stage apparatus 2 including a table member 17 which holds a first object; a liquid recovery port 40 which is provided on the table member and via which a first liquid is recovered; a first flow passage 41 which is formed in the table member, which is connected to the liquid recovery port, and through which a second liquid flows to adjust a temperature of the table member; and a pressure-adjusting device 47 which adjusts a pressure of the first flow passage. The stage apparatus 2 is capable of suppressing the temperature change which would be otherwise caused by the heat of vaporization. An exposure apparatus EX including the stage apparatus 2 is provided.

Fig. 2